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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/777,353	02/12/2004	Kenneth C. Johnson	TWI-30510	5063	
28584 75	590 12/13/2004	EXAMINER			
STALLMAN & POLLOCK LLP SUITE 2200 353 SACRAMENTO STREET SAN FRANCISCO, CA 94111			TSAI, CAROL S W		
			ART UNIT	PAPER NUMBER	
			2857		
			DATE MAILED: 12/13/2004		

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Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)				
	10/777,353	JOHNSON ET AL.				
Office Action Summary	Examiner	Art Unit				
	Carol S Tsai	2857				
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	correspondence address				
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION.  - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statutory period w  - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	6(a). In no event, however, may a reply be tirwithin the statutory minimum of thirty (30) day ill apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	nely filed rs will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).				
Status		!				
1) Responsive to communication(s) filed on 12 Oc	ctober 2004.	•				
,	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.					
Disposition of Claims						
<ul> <li>4)  Claim(s) 1-10 is/are pending in the application.</li> <li>4a) Of the above claim(s) is/are withdraw</li> <li>5)  Claim(s) is/are allowed.</li> <li>6)  Claim(s) 1-10 is/are rejected.</li> <li>7)  Claim(s) is/are objected to.</li> <li>8)  Claim(s) are subject to restriction and/or</li> </ul>	BES	T AVAILABLE COPY				
Application Papers						
9) ☐ The specification is objected to by the Examiner 10) ☑ The drawing(s) filed on 12 February 2004 is/are Applicant may not request that any objection to the o Replacement drawing sheet(s) including the correction 11) ☐ The oath or declaration is objected to by the Examiner	: a)⊠ accepted or b)⊡ objected drawing(s) be held in abeyance. Se on is required if the drawing(s) is ob	e 37 CFR 1.85(a). jected to. See 37 CFR 1.121(d).				
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of:  1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the prior application from the International Bureau * See the attached detailed Office action for a list	s have been received. s have been received in Applicat ity documents have been receive (PCT Rule 17.2(a)).	ion No ed in this National Stage				
Attachment(s)						
1) Notice of References Cited (PTO-892)	4) Interview Summary					
Notice of Draftsperson's Patent Drawing Review (PTO-948)     Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)     Paper No(s)/Mail Date	Paper No(s)/Mail D					

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#### **DETAILED ACTION**

## Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
  - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 1-10 are rejected under 35 U.S.C. 103(a) as being unpatentable over U.S. Patent No. 5,844,684 to Maris et al. in view of U.S. Patent No. 6,211,921 to Maris.

With respect to claims 1 and 5, Maris et al. disclose a method of evaluating a diffracting structure formed on a semiconductor sample comprising the steps of: including interpolation points and associated theoretical optical response characteristics, each interpolation point corresponding to a sample parameter set and with the associated theoretical optical response characteristics being determined by applying a sample model to each of the parameter sets (see Abstract, lines 13-17; col. 4, lines 29-45; and col. 7, line 59 to col. 8, line 21); measuring the actual optical response characteristics of the sample (see col. 4, lines 46-60 and col. 14, line 51 to col. 15, line 8); and iteratively interpolating between the interpolation points using an interpolation model that defines a substantially continuous function which intersects with the interpolation points in order to derive a set of interpolated optical response characteristics that best fit the actual optical response characteristics to evaluate the sample (see col. 3, line 58 to col. 4, line 3; col. 7, lines 46-51; and col. 17, line 64 to col. 18, line 9).

Maris et al. do not disclose creating a database.

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Maris teaches creating a database (see col. 25, lines 11-18).

It would have been obvious to one having ordinary skill in the art at the time the invention was made to modify Maris et al.'s method to include creating a database, as taught by Maris, in order that data can be stored.

As to claims 2 and 6, Maris et al. also disclose the optical response characteristics being in the form of one or both of complex reflectance coefficients and scattering matrices (see col. 15, lines 9-22).

As to claims 3 and 7, Maris et al. also disclose said optical response characteristics being created and measured as a function of wavelength (see col. 7, lines 52-58).

As to claims 4 and 9, Maris et al. also disclose said interpolation model utilizing one or more of linear, multi-cubic, and quadratic functions (see col. 17, lines 6-19).

As to claim 8, Maris et al. also disclose measuring reflectance of the sample (see Abstract, lines 1-5).

As to claim 10, Maris et al. also disclose calculating a theoretical optical signal from the model (see col. 3, lines 41-45).

#### Response to Arguments

3. Applicant's arguments filed October 12, 2004 have been fully considered but they are not persuasive.

Applicants argue that Maris mentions "interpolating between reference samples to obtain an intermediate set of material properties". However, Maris never mentions anything about the type of interpolation he intends to use, that presumably, Maris would use a standard interpolation

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approach which have various drawbacks of the type discussed in the background section of this application, that certainly, Maris contains no suggestion of "interpolating between the interpolation points using an interpolation model that defines a substantially continuous function which intersects with the interpolation points". The Examiner disagrees with Applicants. Since "The interpolation model is used by a fitting optimization algorithm that determines measurement parameters of a sample based on a measured optical signal characteristic of the sample" as described at page 8, lines 23-25 clearly indicates what is meant by interpolation model, as set forth above in the art rejection, Maris et al. do disclose using an interpolation model that defines a substantially continuous function which intersects with the interpolation points in order to derive a set of interpolated optical response characteristics that best fit the actual optical response characteristics to evaluate the sample (see col. 3, line 58 to col. 4, line 3; col. 7, lines 46-51; and col. 17, line 64 to col. 18, line 9).

### **Contact Information**

4. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Carol S. W. Tsai whose telephone number is (571) 272-2224. The examiner can normally be reached on Monday-Friday from 8:30 AM to 5:00 PM. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Marc S. Hoff can be reached on (571) 272-2216. The fax number for TC 2800 is (703) 872-9306. Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the TC 2800 receptionist whose telephone number is (571) 272-1585 or (571) 272-2800.

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In order to reduce pendency and avoid potential delays, Group 2800 is encouraging FAXing of responses to Office actions directly into the Group at (703) 872-9306. This practice may be used for filing papers not requiring a fee. It may also be used for filing papers which require a fee by applicants who authorize charges to a PTO deposit account. Please identify the examiner and art unit at the top of your cover sheet. Papers submitted via FAX into Group 2800 will be promptly forwarded to the examiner.

Carol S. W. Tsai Patent Examiner

US.W.31

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12/08/04